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(54) METHOD FOR PRODUCING OPTICAL SLIT

(57) Abstract:

PROBLEM TO BE SOLVED: To produce an optical slit having a constant slit width with high reproducibility without adjusting the slit width.

SOLUTION: An optically opaque silicon film 2 is deposited on an optically transparent base substrate 1 using a sputter deposition apparatus or the like, and then a portion of the silicon film 2 serving as a passage of light is removed with the specified slit width using a photolithography technique and an etching technique so as to produce the slit 3.

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